Three-Membered Ring Formation by Si...N Interactions in Aminosulfenylsilanes

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The reaction of dimethylaminosulfenylchloride Me₂NSCl with trichlorosilane HSiCl₃ and triethylamine gives elemental sulphur and Me₂NSiCl₃. The aminosulfenylsilane Me₂NSSiCl₃ is postulated to be an intermediate of this reaction. *Ab initio* calculations (MP2/6–311G(d,p)) on Me₂N-S-SiH₃, Me₂N-S-SiH₂Cl, Me₂N-S-SiH₂F, and Me₂N-S-SiCl₃ have been carried out, demonstrating the occurrence of acute valence angles at sulphur and short Si···N distances, which are indicative of NSSi three-membered rings. The strength of the Si···N interactions depends on the electronegativity of the substituent at silicon in *anti*-position to the nitrogen atom and is strongest in the *anti* conformer of Me₂N-S-SiH₂F (< NSSi 68°, Si···N 2.208 Å). The coordination spheres of the nitrogen atoms in the Me₂N-S-SiR₃ molecules are steeply pyramidal, which is in contrast to the planarised N atoms in other SNMe₂ compounds, such as Me₂NSCl. The crystal structure of this compound has been determined, as well as that of the product of the above reaction, Me₂NSiCl₃. Both have planar coordination geometries at the nitrogen atoms.

Key words: Sulfur, Silicon, Crystal Structure

Introduction

Aminoxysilanes R'2N-O-SiR3 have been shown to possess attractive interactions between the silicon and nitrogen atoms, which lead to hypercoordinate Si centres and three-membered ring systems in some extreme cases [1]. Such non-classical bonding was observed to be most pronounced for O-silylhydroxylamines with electronegative substituents bonded to the silicon atoms. SiON triangular structures with acute angles at oxygen have been found in Me₂NOSiF₃ with a short Si···N distance of 1.963(1) Å and a valence angle of $77.1(1)^{\circ}$ in the polar surrounding of the solid state [2]. Weaker interactions are present in isolated molecules in the gas phase (Si···N 2.273(17) Å, < SiON 94.4(9)°). The strength of these Si···N interactions depends also on the position of the electronegative substituent at silicon relative to the donor centre. The vapour of Me₂NOSiH₂Cl comprises two conformers, anti with an NOSiCl torsional angle of 180° having strong Si...N interactions and gauche with an NOSiCl torsional angle of 73° having a 0.308 Å wider Si...N distance and a 17° wider SiON angle [3].

Systems with linking atoms between the Si acceptor and the N donor centres different from oxygen are structurally much less well established.

Silylhydrazines have been investigated and similar effects as described above have been found to be structure-determining in SiNN units [4]. However, in studies on aminomethylsilanes R"₂NCR'₂SiR₃ we could so far not find experimental proof for Si···N interactions, although earlier reports postulated them on the basis of reduced basicities of compounds R"₂NCR'₂SiR₃ as compared to carbon analogues R"₂NCR'₂CR₃ [5].

The aim of this contribution was initially to investigate compounds of the R'₂NSSiR₃ type, *i. e.* aminosulfenylsilanes (silylthiohydroxylamines), as we expected stronger Si···N interactions in such compounds due to the lower bending potential at the sulphur centres. We can show now on a theoretical basis that the Si···N interactions in NSSi systems depend on the same parameters as they do in NOSi systems.

To our knowledge the only Si-S-N compounds reported in the literature are Me₂NSO₂SiMe₃ and Me₂NSSiMe₃ [6], but no synthesis has been published for the latter.

Results

In an attempt to prepare a compound with an Si-S-N linkage which can serve as starting material

for a series of derivatives, we tried to obtain Me₂NSSiCl₃ from the readily available dimethylaminosulfenylchloride under the conditions of a Benkeser type reaction [7], *i.e.* treatment with trichlorosilane and triethylamine. However, the reaction product consisted of elemental sulphur and a colourless liquid, which turned out to be free of sulphur and to contain a direct N-Si bond: Me₂NSiCl₃.

$$\begin{array}{lll} \text{Me}_2\text{N-S-Cl} + \text{HSiCl}_3 + \text{NEt}_3 & -\text{//} & \text{Me}_2\text{N-S-SiCl}_3 \\ & -\text{Me}_2\text{N-SiCl}_3 + \text{S} \end{array}$$

As it seems unlikely that the reactive intermediate of a trichlorosilane/triethylamine mixture (either the anionic Cl₃Si⁻ or the silylene Cl₂Si:) attacks the nitrogen centre of Me₂N-S-Cl, we propose that an intermediate Me₂N-S-SiCl₃ was formed, which decomposed with sulphur extrusion to give Me₂NSiCl₃.

In addition to the spectroscopic identification of the product mixture, the educt Me₂NSCl and the product Me₂NSiCl₃ were characterised structurally by means of X-ray diffraction on single crystals grown from these low melting liquids by insitu methods. These structures will be discussed in the next paragraphs followed by a theoretical

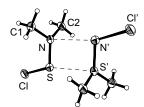


Fig. 1. Molecular structure of Me₂NSCl as obtained by low-temperature single crystal X-ray diffraction.

study of some model compounds containing NSSi units.

Crystal structure of Me₂NSCl. The molecular structure of Me₂NSCl in the crystal is shown in Fig. 1, selected structural parameters are listed in Table 1 together with those calculated ab initio (MP2/6-311G(d,p)) for a monomeric Me₂SNCl unit and a weakly bound dimer in the gas-phase. It is the first experimental structural study on an aminosulfenylchloride in the solid state. The fluorinated (F₃C)₂NSCl was studied by electron diffraction in the gas phase by Oberhammer and co workers [8] and the structural parameters of this study are also given in Table 1. Me₂NSCl crystallises as a weakly bonded dimer with a centre of inversion in the S_2N_2 ring. The $N \cdots S$ contacts are 3.174(1) Å long, which is slightly shorter than the sum of the van-der-Waals radii of 3.39 Å [9]. In the calculated dimer, these weak contacts are predicted to be 2.992 Å, i. e. even shorter than found in the solid state. Otherwise the geometries of the calculated and experimentally examined dimers are very similar, as is obvious from the contents of Table 1.

Unexpectedly, the NSCl angle of $107.1(1)^{\circ}$ is relatively wide, as compared to $(Me_2N)SO_2Cl$

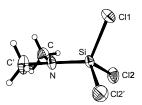


Fig. 2. Molecular structure of Me₂NSiCl₃ as obtained by low-temperature single crystal X-ray diffraction.

Table 1. Geometrical parameters (Å/°) of $(Me_2NSCl)_2$ as determined by low-temperature X-ray crystallography and by *ab initio* calculations of the monomer and dimer on the MP2/6–311G(d,p) level of theory. The last column shows values from the gas-phase electron diffraction (GED) structure determination of $(F_3C)_2NSCl$ for comparison.

	(Me ₂ NSCl) ₂ XRD	$\begin{array}{c} Me_2NSCl \\ MP2/6-311G(d,p) \end{array}$	$(Me_2NSCl)_2 \\ MP2/6-311G(d,p)$	(F ₃ C) ₂ NSCl GED
S-N	1.604(1)	1.630	1.636	1.667(7)
S-Cl	2.171(1)	2.163	2.154	2.090(8)
N-C(1/2)	1.462(1)/1.466(1)	1.465	1.464	1.453(5)
N-S-Cl	107.1(1)	106.1	105.1	98.3(13)
S-N-C(1/2)	120.0(1)/120.0(1)	117.9	117.8	121.5(6)
C-N-C	115.0(1)	113.5	113.6	116.4(18)
$S \cdots N$	3.174(1)	_	2.992	_ ′
$N-S\cdots N$	86.9(1)	_	83.0	_

Table 2. Geometrical parameters (Å/°) of Me₂NSiCl₃ as determined by low-temperature X-ray crystallography (XRD) and gas-phase electron diffraction (GED) [12].

	XRD	GED
Si-N Si-Cl(1)	1.665(3) 2.020(1)	1.657(12) 2.023(5)
Si-Cl(2) N-C Si-N-C	2.043(1) 1.459(3) 123.0(2)	1.446(12) 123.1(8)
C-N-C N-Si-Cl(1)	123.0(2) 112.6(3) 116.7(1)	123.1(8) 113.1(18) 111.3(1)
N-Si-Cl(2)	109.9(1)	111.0(1)

 (103.0°) [10], $(F_3C)_2NSCl$ $(98.2(13)^{\circ})$ [8] or the CISCI angle in SCl₂ (102.71°) [11]. With 1.604(1) Å the S-N bond is shorter than the sum of the covalent radii of sulphur and nitrogen (1.74 Å) [9], but also shorter than in (F₃C)₂NSCl with 1.667(7) Å [8]. This points to some multiple bond character of the S-N bond, resulting in an almost planar coordination geometry at the nitrogen atom, with the sum of angles about it being 354.9(1)°, which was also found in $(F_3C)_2NSCl$ [8]. It also parallels the situation in compounds with the nitrogen atom bonded to silicon (see below) or phosphorus [12]. Expectedly, the differences between the calculated dimer and monomer are very small. The largest difference is an elongation of the S-N bond by as little as 0.006 Å and a compression of the NSCl angle by 1.0°. An estimate of the interaction energy between the two monomers is given by the calculated difference between the energies of dimer and monomer, which is 4.4 kJ/mol at the B3LYP/6-311G(d,p) level of theory and based on fully geometry optimised structures at this level.

Crystal structure of Me_2NSiCl_3 . The molecular structure of Me_2NSiCl_3 was determined earlier in the gas-phase by electron diffraction [13] and we shall refer to this structure of the free molecule in comparison to our new solid state structure. The molecules of Me_2NSiCl_3 lie on a crystallographic mirror plane bisecting the CNC angle and containing one of the chlorine atoms, Cl(1). The molecule has thus C_S symmetry, but no local C_3 symmetry for the $NSiCl_3$ group, as was assumed in the gas phase structure determination. This is manifested by the two different NSiCl angles of $116.7(1)^\circ$ for NSiCl(1) and $109.9(1)^\circ$ for NSiCl(2). Their mean of 112.2° is reasonably close to the reported gas

phase value of 111.3°. The same applies to the different lengths of the Si-Cl bonds of 2.020(1) for SiCl(1) and 2.043(1) Å for SiCl(2), which compares to 2.023(5) Å in the gas phase. The coordination sphere of nitrogen is planar as is indicated by the sum of angles about this atom: 358.6° (gas phase 359.3°). Wide SiNC angles of 123.0(1)° and a smaller CNC angle of 112.6(3)° are observed in the solid state structure. The Si-N distance of 1.665(3) Å represents a short Si-N bond, as is expected for a silylamine with electronegative substituents at the silicon atom.

Including the two structure determinations reported in this paper, structures of the whole series of amino derivatives of chlorinated second octet period element compounds Me₂NSiCl₃, Me₂NPCl₂ [14] and Me₂NSCl are now available and consistently show planar environments of the nitrogen atoms.

Calculations on Si-S-N model compounds. A reaction of Me₂NSCl with HSiCl₃/NEt₃ could involve a Si-S-N three-membered ring intermediate with an Si...N interaction. In order to get an estimate of whether the formation of Si...N interactions is a possibility for the sulphur compounds of this type, Me₂N-S-SiX₃, we calculated the structures of four examples by ab initio methods: Me₂N-S-SiH₃, Me₂N-S-SiH₂Cl, Me₂N-S-SiH₂F and Me₂N-S-SiCl₃. The calculations were performed up to the MP2/6-311G(d,p) level of theory, which turned out to give results closest to experimental gas phase structures for Me₂NOSiF₃. DFT calculations on Me₂NOSiF₃ did not reproduce the experimental gas-phase values and were therefore not applied to the new SiSN systems [2].

The results of the calculations are shown in Fig. 3, and some key parameters are compiled in Table 3. Coordinates of the calculated structures are listed in Table 4.

The calculations show strong deformations of the valence angles at the sulphur atoms in Me₂NS-SiH₃, Me₂NSSiH₂F, Me₂NSSiH₂Cl and Me₂NS-SiCl₃. Expectedly, the weakest Si···N interaction is found in Me₂NSSiH₃, with a Si···N distance of 2.774 Å, which is still below the sum of the vander-Waals radii of 3.54 Å. The angle at sulphur (90.2°) has to be compared with the angle at oxygen in the homologous compound Me₂NOSiH₃, which was determined in a crystal structure to be

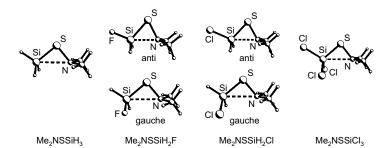


Fig. 3. Molecular structures of Me₂NSSiH₃, Me₂NSSiH₂F, Me₂NSSiH₂Cl and Me₂NSSiCl₃ as obtained by *ab initio* calculations on the MP2/6–311G(d,p) level.

Table 3. Selected geometric parameters (Å/°) and dipole moments [D] for Me_2NSSiH_3 , Me_2NSSiH_2F , Me_2NSSiH_2Cl and $Me_2NSSiCl_3$ as obtained by *ab initio* calculations on the MP2/6-311G(d,p) level. For Me_2NSSiH_2F and Me_2NSSiH_2Cl only the *anti-*conformers are reported.

	Me ₂ NSSiH ₃	Me ₂ N	NSSiH ₂ F	Me ₂ NSSiH ₂ Cl		Me ₂ NSSiCl ₃
		anti	gauche	anti	gauche	
Si-S	2.134	2.129	2.112	2.120	2.116	2.098
S-N	1.766	1.790	1.766	1.784	1.764	1.762
Si···N	2.774	2.208	2.750	2.315	2.762	2.675
Si-S-N	90.2	68.0	89.9	72.2	90.3	87.3
S-N-C	110.5	112.2	110.4/110.5	111.9	110.5/110.6	110.9
C-N-C	110.8	112.3	111.0	112.0	110.0	111.3
μ	1.33	4.40	1.88	4.73	2.20	3.42

102.6(1)° [15], bearing in mind that valence angles at sulphur are generally smaller in homologous compounds.

As found experimentally for the SiON compounds Me₂NOSiF₃ [2] and Me₂NOSiH₂Cl [3] and predicted theoretically for Me₂NOSiH₂F [16], substitution of the silicon bound hydrogen atoms for electronegative substituents leads to a drastic decrease of the SiON angle. Our new calculations predict a similar behaviour for the thiohydroxylamines. The valence angle at the sulphur atoms in the anti conformers of Me₂NSSiH₂F and Me₂NS-SiH₂Cl are calculated to be as small as 68.0 and 72.2°, corresponding to Si···N distances of 2.208 and 2.315 Å, respectively. The calculated values for the oxygen analogues anti-Me2NOSiH2F and anti-Me₂NOSiH₂Cl are 2.229 and 2.259 Å, i. e. very similar. Note that all these are gas-phase values and even stronger interactions have to be anticipated for solution, in particular for polar solvents or the solid state, as was shown to be the case for Me₂NOSiF₃ (<SiON gas phase 94.4(9), solid state $77.1(1)^{\circ}$) [2] and Me₂NOSiH₂Cl (<SiON gas phase 104.7(10), solid state $79.7(1)^{\circ}$) [3].

In the *gauche* conformers of Me₂NSSiH₂F and Me₂NSSiH₂Cl the corresponding NSSi angles are

much larger than in the *anti* conformers (89.9 and 90.3°), which represents a widening of 21.9 and 18.1°, respectively. Similar behaviour was also observed for Me₂NOSiH₂Cl, which has an SiON angle 17° wider in the *gauche*- than in the *anti*-conformer. Despite these large structural differences between the conformers, their energies are surprisingly similar. In both cases, Me₂NSSiH₂F and Me₂NSSiH₂Cl, the *anti*-conformers represent the ground state, but the *gauche*-conformers are only 4 and 5 kJ mol⁻¹ higher in energy.

The SiSN angle in Me₂NSSiCl₃ is predicted to be as much as 15° larger than in Me₂NSSiH₂Cl, an effect which was found earlier for the pair of hydroxylamines Me₂NOSiCl₃ [17] and Me₂NOSiH₂Cl [3]. It is probably due to the steric requirement of the comparably large Cl atoms at the silicon centre, which make an increase of the coordination number less favourable.

The molecular dipole moments have also been calculated and are strongly dependent on the substituents at silicon. The highest dipole moment of 4.73 D is found for Me₂NSSiH₂Cl, the smallest of 1.33 D for Me₂NSSiH₃.

The $Si \cdots N$ interactions in SiSN compounds lead to a distortion of the coordination geometries at

Table 4. Coordinates for Me_2NSSiH_3 , Me_2NSSiH_2F , Me_2NSSiH_2Cl and $Me_2NSSiCl_3$ as obtained by *ab initio* calculations on the MP2/6-311G(d,p) level.

	Me_2NSSiH_3		anti	-Me ₂ NSSi	H ₂ F	anti-	Me ₂ NSSi	GiH ₂ Cl		$Me_2NSSiCl_3$		
Si1	0.000	0.000	0.000	0.788	- 0.990	0.000	0.000	0.000	0.000	0.000	0.749	0.000
S2	0.000	0.000	2.134	-1.207	-0.248	0.000	0.000	0.000	2.120	1.396	-0.817	0.000
N3	1.766	0.000	2.139	0.000	1.073	0.000	1.699	0.000	1.573	0.026	- 1.926	0.000
H/F/Cl4	- 1.411	0.000	-0.439	0.733	-2.617	0.000	-1.962	0.000	-0.706	1.041	2.502	0.000
H/Cl5	0.679	-1.207	-0.501	1.482	-0.658	1.250	0.576	-1.240	-0.527	- 1.191	0.716	1.647
H/Cl6	0.679	1.207	-0.501	1.482	-0.658	-1.250	0.576	1.240	-0.527	-1.191	0.716	-1.647
C7	2.277	1.205	2.795	-0.068	1.887	- 1.216	2.406	1.215	1.986	0.022	-2.753	- 1.210
C8	2.277	-1.205	2.795	-0.068	1.887	1.216	2.406	- 1.215	1.986	0.022	-2.753	1.210
H9	1.907	2.087	2.271	0.032	1.238	-2.087	1.866	2.088	1.618	-0.011	-2.110	-2.090
H10	3.369	1.189	2.736	0.760	2.602	-1.200	3.406	1.197	1.543	-0.880	-3.371	-1.190
H11	1.977	1.271	3.853	-1.021	2.429	-1.283	2.492	1.284	3.079	0.905	-3.406	-1.275
H12	1.907	-2.087	2.271	0.033	1.238	2.087	1.866	-2.088	1.618	- 0.011	-2.110	2.090
H13	3.369	-1.189	2.737	0.760	2.602	1.200	3.406	- 1.197	1.543	-0.880	-3.371	1.190
H14	1.977	- 1.271	3.853	- 1.021	2.429	1.283	2.492	- 1.284	3.079	0.905	- 3.406	1.275

	gauch	e-Me ₂ NSS	SiH ₂ F	gauche-Me ₂ NSSiH ₂ Cl			
Si1	- 1.611	- 0.377	0.297	- 1.183	- 0.903	0.274	
S2	0.126	-0.796	-0.828	0.630	-0.904	-0.817	
N3	1.077	0.200	0.278	1.292	0.323	0.263	
H4	-2.717	-1.144	-0.298	-2.044	- 1.948	-0.300	
F5/Cl5	- 1.989	1.191	0.200	-2.198	0.878	0.104	
H6	- 1.389	- 0.699	1.709	-0.912	- 1.117	1.698	
C7	2.180	-0.578	0.845	2.490	-0.179	0.939	
C8	1.575	1.396	-0.408	1.583	1.555	-0.473	
H9	1.778	- 1.436	1.386	2.236	-1.073	1.512	
H10	2.720	0.063	1.548	2.840	0.596	1.627	
H11	2.883	-0.938	0.078	3.300	-0.427	0.236	
H12	0.729	1.970	-0.788	0.669	1.922	-0.940	
H13	2.116	2.003	0.324	1.938	2.301	0.244	
H14	2.250	1.155	- 1.244	2.350	1.412	- 1.251	

the nitrogen and silicon atoms. The nitrogen atoms in all calculated compounds adopt steeply pyramidal coordination geometries with sums of angles between 331.8 (Me₂NSSiH₃) and 336.5° (anti-Me₂NSSiH₂F), which is clearly at variance with the strongly planarised nitrogen atom in Me₂NSCl (sum of angles 355°) and other Me₂NS-compounds.

The pre-coordination of the Si···N type in the SiSN compounds makes the process of sulphur extrusion from the compound Me₂NSSiCl₃ quite likely, if a process exists in which the sulphur atom can be transferred. Insertion into an existing S-S chain could be such a possibility, but much more experimental and theoretical work has to follow to verify such a working hypothesis. However, it would be a possible explanation for our experimental observation that Me₂NSCl reacts with

H₃SiCl and NEt₃ to give Me₂NSiCl₃ and sulphur with Me₂NSSiCl₃ as a transient species.

Experimental Section

Aminosulfenylchloride was prepared as described in the literature [18].

Reaction of Me₂NSCl with ClH₃Si and NEt₃: Under rigorous inert gas conditions triethylamine (9.6 mL, 70 mmol) and Me₂NSCl (6.7 g, 70 mmol) were dissolved in diethyl ether (150 mL) and cooled to – 10 °C. HSiCl₃ (7.8 ml) was added dropwise, whereupon a colourless precipitate formed and the yellow-orange solution became pale yellow. The mixture was filtered and the residue washed with two times 10 ml of ether. The solvent was removed from the ether phase by distillation over a 10 cm Vigreux column. The distillation residue, a yellowish liquid containing some solid, was

condensed into a cold trap in vacuum. It was identified by ¹H NMR, ²⁹Si NMR, GC-MS and X-ray crystallography as Cl₃SiNMe₂.

Crystal structure determination of Me₂NSCl and Me₂NSiCl₃. Single crystals of Me₂NSCl and Me₂N-SiCl₃ were grown *in situ* on the diffractometer by slowly cooling the melt in a sealed capillary below the melting point after generation of a suitable seed crystal. Data collection was undertaken with a Nonius Turbo-CAD4 diffractometer.

Crystal data Me₂NSCl, C₂H₆NSCl, $M_{\rm r}$ = 111.59, crystal system monoclinic, space group $P2_1/c$, Z = 4, a = 5.8213(3), b = 10.7705(7), c = 8.3786(6) Å, β = 101.419(5)°, V = 514.93(6) ų at 133(2) K, μ = 0.976 mm⁻¹. $2\theta_{\rm max.}$ = 70°, ω -scan, 8741 scattering intensities collected of which 2244 were unique [$R_{\rm int}$ = 0.1072], 70 parameters, R_1 = 0.0332 for 2038 reflections with $F_{\rm o}$ > 4 $\sigma(F_{\rm o})$ and wR_2 = 0.0880 for all 2244 data.

Crystal data Me₂NSiCl₃, C₂H₆NSiCl₃, $M_r = 178.52$, crystal system monoclinic, space group P_1/m , Z = 2, a = 6.086(1), b = 10.450(2), c =

6.334(1) Å, β = 111.86(1)°, V = 373.90(6) ų at 143(2) K, μ = 1.279 mm⁻¹. $2\theta_{\text{max.}}$ = 54°, ω -scan, 862 scattering intensities collected of which 793 were unique [R_{int} = 0.0345], 49 parameters, R_1 = 0.0456 for 740 reflections with F_{o} > 4 $\sigma(F_{\text{o}})$ and wR_2 = 0.1268 for all 793 data.

Structure solutions and refinements were undertaken with the program SHELXTL 5.01 [19]. Crystallographic data (excluding structure factors) have been deposited with the Cambridge Crystallographic Data Centre as supplementary publication no. CCDC-204077 (Me₂NSCl) and CCDC-204078 (Me₂NSiCl₃). Copies of the data can be obtained free of charge on application to CCDC, 12 Union Road, Cambridge CB2 1EZ, UK (E-mail: deposit@ccdc.cam.ac.uk).

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